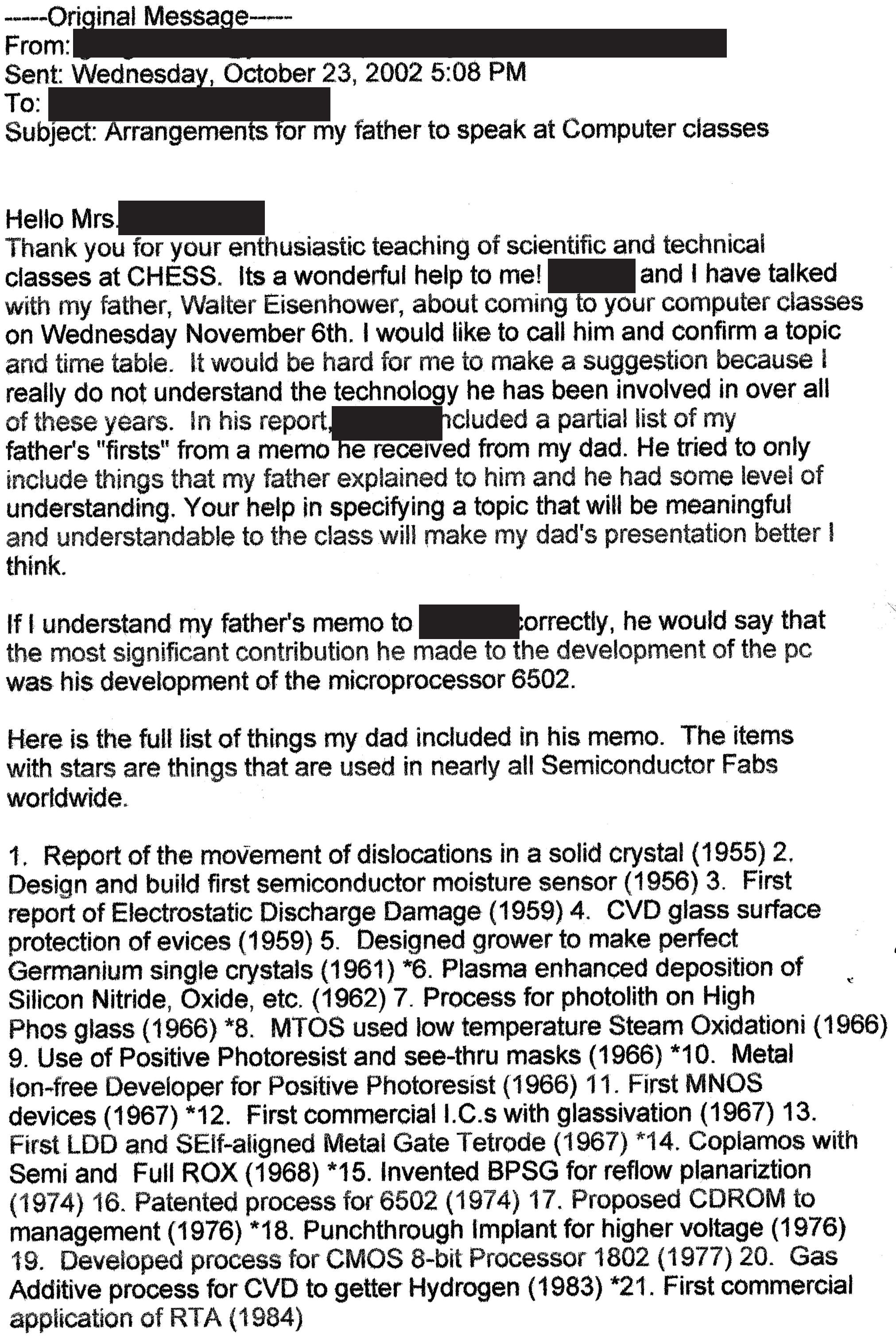
The following email was sent to Walt's grandson's teacher by his daughter, listing her father's various semiconductor-related inventions and innovations.



-----Original Message-----
From: [redacted]
Sent: Wednesday, October 23, 2002 5:08 PM
To: [redacted]
Subject: Arrangements for my father to speak at Computer classes

Hello Mrs. [redacted]
Thank you for your enthusiastic teaching of scientific and technical classes at CHESS. Its a wonderful help to me! [redacted] and I have talked with my father, Walter Eisenhower, about coming to your computer classes on Wednesday November 6th. I would like to call him and confirm a topic and time table. It would be hard for me to make a suggestion because I really do not understand the technology he has been involved in over all of these years. In his report, [redacted] included a partial list of my father's "firsts" from a memo he received from my dad. He tried to only include things that my father explained to him and he had some level of understanding. Your help in specifying a topic that will be meaningful and understandable to the class will make my dad's presentation better I think.

If I understand my father's memo to [redacted] correctly, he would say that the most significant contribution he made to the development of the pc was his development of the microprocessor 6502.

Here is the full list of things my dad included in his memo. The items with stars are things that are used in nearly all Semiconductor Fabs worldwide.

1. Report of the movement of dislocations in a solid crystal (1955) 2.
Design and build first semiconductor moisture sensor (1956) 3. First
report of Electrostatic Discharge Damage (1959) 4. CVD glass surface
protection of evices (1959) 5. Designed grower to make perfect
Germanium single crystals (1961) *6. Plasma enhanced deposition of
Silicon Nitride, Oxide, etc. (1962) 7. Process for photolith on High
Phos glass (1966) *8. MTOS used low temperature Steam Oxidationi (1966)
9. Use of Positive Photoresist and see-thru masks (1966) *10. Metal
Ion-free Developer for Positive Photoresist (1966) 11. First MNOS
devices (1967) *12. First commercial I.C.s with glassivation (1967) 13.
First LDD and SElf-aligned Metal Gate Tetrode (1967) *14. Coplamos with
Semi and Full ROX (1968) *15. Invented BPSG for reflow planariztion
(1974) 16. Patented process for 6502 (1974) 17. Proposed CDROM to
management (1976) *18. Punchthrough Implant for higher voltage (1976)
19. Developed process for CMOS 8-bit Processor 1802 (1977) 20. Gas
Additive process for CVD to getter Hydrogen (1983) *21. First commercial
application of RTA (1984)

Thursday, October 24, 2002 CompuServe: ZOOTANDELLIE